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Picosun Board of Directors

THE ALD DREAM TEAM

Atomic Layer Deposition was invented in 1974 by Dr. Tuomo Suntola, Member of the Picosun Board of Directors. Our CTO Sven Lindfors has designed outstanding ALD systems continuously since 1975. Combined, Picosun people share over 200 years of ALD experience forming what many describe as "by far, the best ALD team ever". We have contributed to more than 100 patents on ALD. Our comprehensive background establishes Picosun as the optimal partner for your ALD technology needs!



Tuomo Suntola

- Inventor of the Atomic Layer Deposition method in 1974.
- Developer of ALD with potential for electro-luminescent flat panel display application 1974 – 1977.
- The head of flat panel display division at Lohja Oy 1977 – 1987.
- Founder and Directing Manager of Microchemistry Ltd. 1987 – 1997.
- Initiator for the expansion of ALD technology to semiconductor applications and catalytic surface fabrication.
- R&D Fellow at Neste Oy and Senior Scientific Advisor at Fortum Oyj 1998 – 2003. Emphasis on sustainable energy future.
- Chief Scientific Advisor of Picosun Oy through Suntola Consulting Ltd. 2004 – 2007. Member of the Picosun Board of Directors since June 2007.



Sven Lindfors

CTO of Picosun

Has significantly contributed to the design and development of

- ALD production tools at Lohja Oy 1975 – 1987.
- ALD R&D tools at Microchemistry Ltd. 1987 – 1999.
- ALCVD™ R&D and production tools at ASM Microchemistry Ltd. 1999 – 2003.
- SUNALE™ research and production ALD tools at Picosun since 2004.

*Picosun Headquarters
at Micronova research
center in Espoo, Finland.*



The future of thin films is here

Atomic Layer Deposition has gained enormous attention during the past few years. The ALD method has been adopted in HVM production of microprocessors, DRAM memories, optoelectronic read heads and TFEL flat panel displays. ALD is the key enabling thin film technology in all future micro- and nanotechnology applications.

Ultimate ALD solutions

Picosun has designed ALD process tools with unique scalability from research to production. SUNALE™ ALD systems offer unmatched quality and productivity. Our long history and comprehensive background establishes Picosun as the optimal partner for your ALD technology needs. SUNALE™ ALD process tools are used by leading scientific institutions in Europe, America and Asia.





SEMI organisation President and CEO Stanley T. Myers presents the European SEMI 2004 award to Dr. Tuomo Suntola at Semicon Europa 2004 exhibition in Munich.

PICOSUN – THE ALD POWERHOUSE

SUNALE™ R-series ALD systems are designed with pioneering ALD experience to fulfill even the most stringent research requirements. They offer unmatched quality, reliability and productivity. SUNALE™ R-series ALD tools invite corporate funding for research projects because of their unique scalability from research to production.

Picosun focuses exclusively on ALD systems. SUNALE™ P-series ALD equipment offer fast and safe processing capability. The modern compact design of our reactors saves expensive production space.

SUNALE™ ALD process tools are used by leading scientific institutions and companies across Europe, America and Asia.



Main Headquarters

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Regional sales

See www.picosun.com/contact/
for details of regional sales offices.